Thickness-dependent optical constants of SnO_2 thin films on Si grown by atomic layer deposition

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Supplemental Document

Figure 1 shows the comparison of the thickness dependence of the dielectric function (left-real part and right-imaginary part) of the SnO_2 as a function of photon energy.

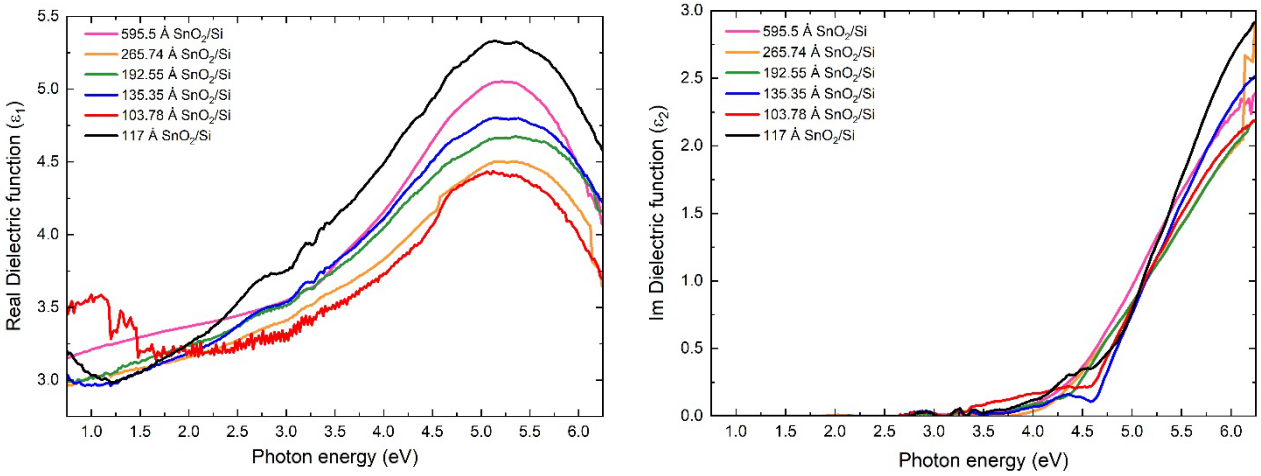

Figure 1: Comparison of the thickness dependence of the real part (left) and imaginary part (right) of the dielectric function of the SnO_2 film layer as a function of photon energy.